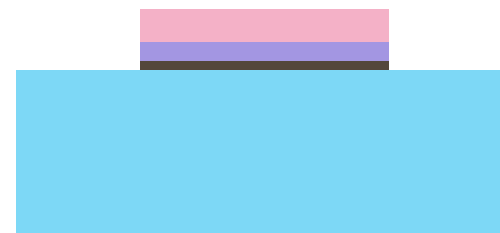




(a) Spin-coat AZ4210



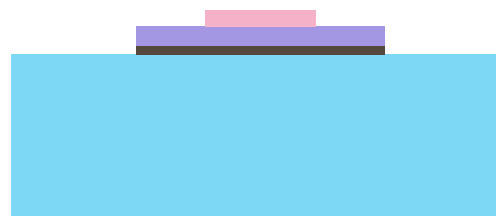
(b) Photolithography  
for canvas protection



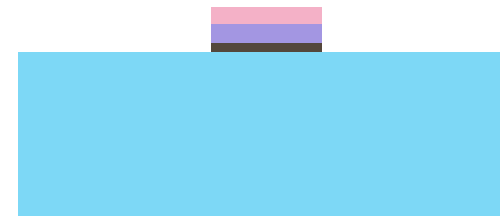
(c) RIE etching



(d) Wash off AZ4210,  
spin-coat AZ4110



(e) Photolithography  
for Hall bar protection



(f) Oxygen plasma  
barrel etching



(g) Wash off AZ4110



(h) Remove Hyflon

